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Silicon Sensors Development: the INFN-FBK Collaboration

The development of silicon sensors typically requires the iteration through several prototypes to advance their design and fabrication process. The access to a fabrication clean room providing both customized design and fabrication process to address the needs of a particular project is however typically restricted by the sensor fabrication costs and availability of institutes with the necessary facilities. Fondazione Bruno Kessler (FBK) is a research institute operating a 6 inch CMOS-like fabrication line with all the necessary steps for the production of silicon sensors. FBK and INFN started a collaboration in 2003 to facilitate the access of the INFN research groups to the silicon sensors fabrication capabilities of FBK. Several sensor technologies are being advanced within this collaboration, like pixel, strip, 3D, LGAD, SiPM, and SDDs. In addition to the development of silicon sensors, within the collaboration, the FBK facilities are used also for the fabrication of MEMS, photonic, and quantum devices. This talk gives an overview of the fabrication capabilities of FBK and the INFN-FBK collaboration. Selected project highlights will be presented.

Title

Topic

Solid state sensors

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